

| Ref # | Hits | Search Query   | DBs                    | Default Operator | Plurals | Time Stamp       |
|-------|------|--|------------------------|------------------|---------|------------------|
| L1    | 6943 | polysilicon and (SiO <sub>2</sub> ?sub?xN?xub?y or silicon near oxynitride or (nitrided near (silicon near (dioxide or oxide))))   | US-PGPUB; USPAT; USOCR | OR               | OFF     | 2006/01/20 07:23 |
| L2    | 3    | I1 and plasam  | US-PGPUB; USPAT; USOCR | OR               | OFF     | 2006/01/20 07:23 |
| L3    | 4979 | I1 and plasma  | US-PGPUB; USPAT; USOCR | OR               | OFF     | 2006/01/20 07:23 |
| L4    | 319  | I3 and processing near chamber   | US-PGPUB; USPAT; USOCR | OR               | OFF     | 2006/01/20 07:23 |
| S1    | 160  | nitrided near (silicon near oxide or SiO <sub>2</sub> ?sub?2) and plasma   | US-PGPUB; USPAT; USOCR | OR               | OFF     | 2006/01/19 17:07 |
| S2    | 27   | ("4621277"   "4623912"   "4913929"   "5445999"   "5455204"   "5834353"   "5861651"   "5891809"   "5939763"   "6013553"   "6048769"   "6060369"   "6060403"   "6087236"   "6096614"   "6184110"   "6228779"   "6239044"   "6245689"   "6248628"   "6251761"   "6265327"   "6294819"   "6306741"   "6548366"   "6566205").PN. OR ("6780720").URPN. | US-PGPUB; USPAT; USOCR | OR               | OFF     | 2006/01/19 09:16 |
| S3    | 91   | ("4913929").URPN.  | USPAT                  | OR               | OFF     | 2006/01/19 10:08 |
| S4    | 1    | "6265327".pn.  | USPAT                  | OR               | OFF     | 2006/01/19 10:08 |
| S5    | 31   | ("4135097"   "4147573"   "4179312"   "4870030"   "4929986"   "5055696"   "5180435"   "5334554"   "5569499"   "5672521"   "5716870").PN. OR ("6265327").URPN.   | US-PGPUB; USPAT; USOCR | OR               | OFF     | 2006/01/19 11:52 |
| S6    | 1    | "20020197884".pn.  | US-PGPUB; USPAT; USOCR | OR               | OFF     | 2006/01/19 11:58 |
| S7    | 0    | ep1326271.pn.  | EPO; JPO; DERWENT      | OR               | OFF     | 2006/01/19 11:59 |
| S8    | 0    | ep1326271  | EPO; JPO; DERWENT      | OR               | OFF     | 2006/01/19 11:59 |
| S9    | 0    | EP1326271  | EPO; JPO; DERWENT      | OR               | OFF     | 2006/01/19 12:00 |
| S10   | 0    | EP01326271   | EPO; JPO; DERWENT      | OR               | OFF     | 2006/01/19 12:01 |

|     |       |  |                        |    |     |                  |
|-----|-------|--|------------------------|----|-----|------------------|
| S11 | 34    | nitrided near silicon near (dioxide or oxide)  | EPO; JPO; DERWENT      | OR | OFF | 2006/01/19 12:00 |
| S12 | 0     | EP0001326271   | EPO; JPO; DERWENT      | OR | OFF | 2006/01/19 12:01 |
| S13 | 0     | EP0001326271.pn.   | EPO; JPO; DERWENT      | OR | OFF | 2006/01/19 12:01 |
| S14 | 0     | "2001049186".pn.   | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/01/19 12:02 |
| S15 | 7     | "1326271"  | EPO; JPO; DERWENT      | OR | OFF | 2006/01/19 12:28 |
| S16 | 31712 | gate near dielectric or insulator same apparatus                                     | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/01/19 12:29 |
| S17 | 430   | gate near (dielectric or insulator) same apparatus                                   | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/01/19 12:29 |
| S18 | 3     | S17 and nitrided near silicon near (dioxide or oxide)                                | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/01/19 12:30 |
| S19 | 0     | integrated near processing near system]  | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/01/19 12:30 |
| S20 | 493   | integrated near processing near system   | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/01/19 12:30 |
| S21 | 221   | S20 and processing near chamber  | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/01/19 13:08 |
| S22 | 3     | S21 and (silicon near (oxynitride or nitrided)) near silicon near (oxide or dioxide) | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/01/19 12:33 |
| S23 | 2224  | S21 vand SiO <sub>x</sub> N <sub>y</sub>   | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/01/19 12:33 |
| S24 | 6     | S21 and SiO <sub>x</sub> N <sub>y</sub>  | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/01/19 12:33 |
| S25 | 0     | "2001049186".pn.   | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/01/19 13:09 |
| S26 | 1     | "20010049186".pn.  | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/01/19 13:11 |
| S27 | 2     | "06140392".pn.   | EPO; JPO; DERWENT      | OR | OFF | 2006/01/19 15:09 |

|     |       |   |                              |    |     |                  |
|-----|-------|---|------------------------------|----|-----|------------------|
| S28 | 7777  | gate near insulator   | US-PGPUB;<br>USPAT;<br>USOCR | OR | OFF | 2006/01/19 15:10 |
| S29 | 23154 | S28 processing near chamber   | US-PGPUB;<br>USPAT;<br>USOCR | OR | OFF | 2006/01/19 15:11 |
| S30 | 111   | S28 and processing near chamber   | US-PGPUB;<br>USPAT;<br>USOCR | OR | OFF | 2006/01/19 15:11 |
| S31 | 14    | ("5413664"   "5529630"   "5578520"<br>  "5648276"   "5811328"  <br>"5840118"   "5851860"   "5953595"<br>  "5956581"   "6063654"  <br>"6080643"   "6348369"  <br>"6444506").PN. OR ("6673126").<br>URPN. | US-PGPUB;<br>USPAT;<br>USOCR | OR | OFF | 2006/01/19 15:14 |
| S32 | 43    | ("5578520").URPN.   | USPAT                        | OR | OFF | 2006/01/19 15:23 |
| S33 | 14    | ("6329229").URPN.   | USPAT                        | OR | OFF | 2006/01/19 15:28 |
| S34 | 211   | multi near chamber and silicon near<br>oxynitride   | USPAT                        | OR | OFF | 2006/01/19 15:28 |
| S35 | 218   | nitrided near (silicon near oxide or<br>SiO <sub>2</sub> ) and (heat\$3 or<br>anneal\$3)  | US-PGPUB;<br>USPAT;<br>USOCR | OR | OFF | 2006/01/19 17:08 |
| S36 | 44    | nitrided near (silicon near oxide or<br>SiO <sub>2</sub> ) and ((heat\$3 or<br>anneal\$3)same ammonia)  | US-PGPUB;<br>USPAT;<br>USOCR | OR | OFF | 2006/01/19 17:09 |
| S37 | 65    | ("5397720"   "5403786").URPN.   | USPAT                        | OR | OFF | 2006/01/19 17:14 |